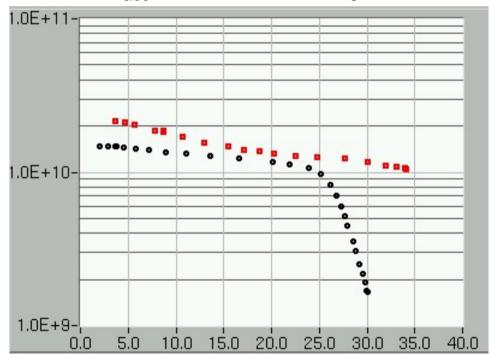
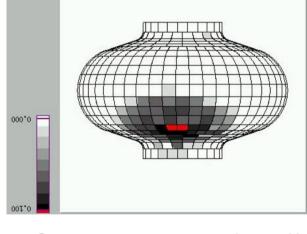
1DE1: First DESY-Cavity successful

- 1DE1: First Cavity of DESY inhouse fabrication (deepdrawing at Zanon)
- 150µm EP@Henkel, 800C, 130µm EP@Henkel, HPR + bake (add. HPR after bake necessary due to fieldemission)

 $E_{acc} = 34 \text{ MV/m} @ Q_0 = 1.10^{10}$; no FE; limited by BD; few MP



Q(E)-curves before and after bake at T = 2K Detlef Reschke



Quench location far off the equator



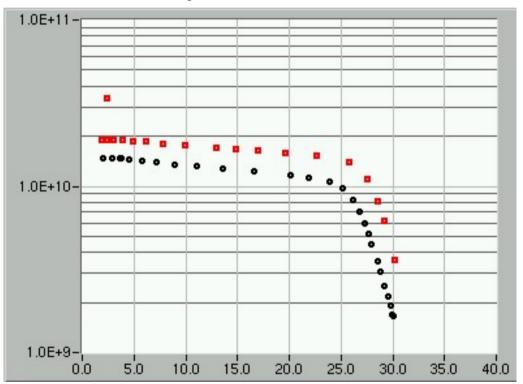
1DE1: detailed history

- Cavity made of Heraeus sheets; production 1999
- Deepdrawing of cups at Zanon Co.
- Complete machining and electron beam welding at DESY
- Electropolishing before test 1 at Henkel Co.;
 EP + initial HPR before test 4 at Saclay
- HPR, assembly and test at DESY (CTA and hall 3)



1DE1: EP treatment at Saclay, test 4

- add. final EP of 42μm, ethanol rinse + HPR at Saclay; add. HPR at DESY: E_{acc} = 30,2 MV/m @Q₀ = 3,6 ·10⁹; no FE; limited by Quench (no T-maps)



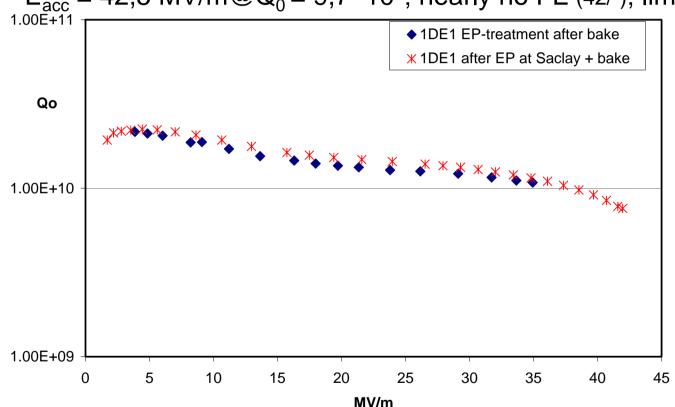
Q(E) at 2 K **before bake** after first EP (black) + after EP at Saclay (red)

=> Quench after EP at Saclay at 30MV/m => needs to be confirmed by test after bake

1DE1: EP treatment at Saclay + bake, test 5

Test 5: add. 120C / 48h bake at DESY:

 $E_{acc} = 42.5 \text{ MV/m} @ Q_0 = 9.7 \cdot 10^9$; nearly no FE (42/-); limited by BD (T-maps)



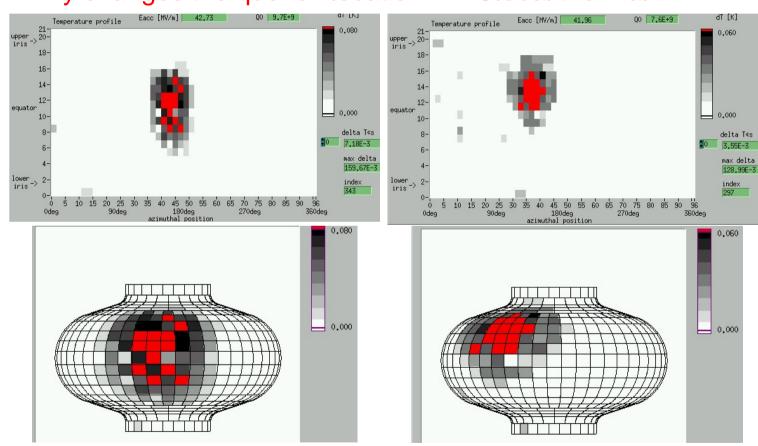
Q(E) at 2 K after bake after first EP (black) + after EP at Saclay (red)

=> Improvement of 7 MV/m compared to first EP



1DE1: details of test 5

- test 5: add. 120C / 48h bake: T-maps at 1.8K (left) + 2K (right) during quench Why changes the quench location??? Global thermal BD??









1DE1: details of test 4 (EP at Saclay)

- Main parameters of EP at Saclay:
 constant voltage operation; T < 30°C, new bath 1 vol HF 40% 9 vol
 H₂SO₄ 95%, ethanol rinse 26 min
- additional description by F. Eozenou, Oct. 06: "We polished yesterday 1DE1 cavity during about 1h30. 17 Volts, 1 tr/min, T about 30°C. About 55g of niobium were dissolved. The cavity is very shiny. Shininess has been improved. It has undergone an ethanol rinse and a HPR."
- Removal rate is 42 μm for 1,3 g/μm.
- HPR at hall 3 and test done:
 - => no Q-disease
 - => Quench at 30MV/m; needs to be confirmed by test after bake
 - => improved Q-value at 2K
 - => RRR measured during cooldown with average value 287

1DE1 more rf data

	Test 1 final 80µm EP, HPR	Test 2 bake 127C, 48h	Test 3 only HPR (Q(T) incomplete)	Test I/II in Saclay
R _{res} fit	(1,97) n Ω (fit not good)	4,97 nΩ	(1,44) nΩ	-
Δ/k_BT_C $(T_C = 9,2K)$	1,9	1,91	(1,58)	-
Q _{BCS} (4,3K)	3,88 -10 ⁸	5,67 -10 ⁸	Not measured	-
Q _{0,max} (1,8K)	3,4 ·10 ¹⁰	3,88 -10 ¹⁰	3,28 ·10 ¹⁰	3,0 / 3,0 -1010
$Q_0(E_{acc} = 23.5 \text{ MV/m}; 1.8K)$	1,7 -10 ¹⁰	1,7 -10 ¹⁰	2,0 ·10 ¹⁰	1,2 / 1,6 ·10 ¹⁰

1DE1 more rf data II

	Test 4 final 42 µm EP at Saclay, HPR	Test 5 After 120C/48h bake at DESY	Test	Test
R _{res} fit	3,83 nΩ	5,7 n Ω	nΩ	-
Δ/k_BT_C ($T_C = 9,2K$)	1,95	1,9	(-
Q _{BCS} (4,3K)	Not measured	6,8 ·10 ⁸		-
Q _{0,max} (1,8K)	3,4 ·10 ¹⁰	3,6 ·10 ¹⁰	-10 ¹⁰	·10 ¹⁰
$Q_0(E_{acc} = 23.5 \text{ MV/m}; 1.8 \text{K})$	2,5 ·10 ¹⁰	2,5 ·10 ¹⁰	-10 ¹⁰	·10 ¹⁰

X-Ray Free-Electron Laser 23.01.2007 10